What is claimed is:

1. A method of fabricating an electrode of a plasma display panel using a photo peeling method, comprising the steps of:

forming a photo material layer on a substrate, the adhesive strength of the photo material layer decreases when exposed to light;

exposing the photo material layer to light in correspondence to a desire pattern;

forming an electrode material layer on the exposed photo material layer;

forming a peeling material layer on the electrode material layer, the peeling material layer has higher adhesive strength than an exposure area of the photo material layer; and

taking off the peeling material layer to pattern the electrode material layer.

2. The method according to claim 1, wherein the exposure area of the electrode material layer is removed when taking off the peeling material layer.

3. The method according to claim 1, further includes the step of:

firing the remaining area except where the electrode material layer is removed by the peeling material layer.

4. The method according to claim 1, wherein the photo material layer includes:

binder of 20 ~ 50 wt%;

reactive monomer of 40 ~ 70 wt%;

photo initiator of 2 ~ 5 wt%; and

additive of 2 ~ 5 wt%.

5. The method according to claim 4, wherein the binder includes at least one of polyurethane, Polyester, polyacrylate, co-polymer with carboxylic -COOH and radical OH or tri-polymer with carboxylic -COOH and radical OH.

6. The method according to claim 4, wherein the reactive monomer includes at least one of a multi-functional monomer with 2 ~ 5 reactive radicals, acrylic monomer or urethane monomer and oligomer.

7. The method according to claIm 4, wherein the photo initiator includes at least one of 1-hydroxy-cyclochexyl-phenyl ketone, p-pheny benzo phenone, benzyldimethylketal, 2, 4-dimethylthioxanthone, 2, 4-diethylthioxanthone, benzoin ethyl ether, benzoin isobutyl ether, 4,4'-diethylaminohenzophenone, p-dimethyl amino benzoic acid ethylester.

8. The method according to claim 5, wherein the additive includes at least one of dispersing agent, stabilizer and polymerization prohibiting agent.

9. The method according to claim 1, wherein the electrode material layer includes:

silver Ag powder of 90 ~ 99 wt%; and

glass-frit of 1 ~ 10 w-t%.

10. The method according to claim 1, wherein the peeling material layer includes:

binder of 70 ~ 80 wt%; and

additive of 20 ~ 30 wt%.

11. The method according to claim 10, wherein the binder includes at least one of polyurethane, Polyester, polyacrylate, co-polymer with radical OH or tri-polymer with radical OH.

12. The method according to claim 10, wherein the additive includes at least one of dispersing agent, stabilizer or adhesive.